

Ultra Precision Manufacturing Conference 2015 Tuesday 12 May 2015

Institute for Manufacturing, Cambridge, Lecture Theatres

Agenda

08:45 – 09:15	Arrival and Registration
09:15 – 09:30	Welcome and Introduction Conference Team
09:30 - 09:50	Introduction to the TRL (Technology Readiness Level) Martin O'Hara, National Strategy Manager EPSRC Centre for Innovative Manufacturing in Ultra Precision
09:50 – 10:10	How to Approach the Next Generation of Optical Instruments Prof. Richard Leach, University of Nottingham
10:10 – 10:30	The Latest Advances in High Precision Laser Micromachining Alan Ferguson, Oxford Lasers
10:30 – 11:00	BREAK
11:00 – 12:20	Ultra Precision PhD Presentations Centre for Innovative Manufacturing and Centre for Doctoral Training in Ultra Precision PhD Students
12:20 – 13:20	Networking Lunch
13:20 – 13:40	Nano Ploughing – A Scale Up Nanofabrication Method Dr. Sun Jining, Heriot-Watt University
13:40 – 14:00	Nanoanalysis in the SEM: From Nanolayer Down to Single Atoms Christian Lang, Oxford Instruments
14:00 – 14:20	Nano-Metrology: X-rays, Optical Interferometry, AFM Metrology and Nano Positioning Andrew Yacoot, National Physical Laboratory (NPL)
14:20 – 14:40	AFM Probed-Based Machining Dr. Emmanuel Brousseau, Cardiff University
14:40 – 15:10	BREAK
15:10 – 15:30	Challenges in Geometrical Metrology for Additive Manufacturing Prof. Xiangqian (Jane) Jiang, University of Huddersfield
15:30 – 15:50	Engineering of Surface using Laser-Initiated Liquid-Assisted Colloidal Lithography Dr. Magdalena Ulmeanu, University of Bristol
15:50 – 16:10	Ultra Precision Machining for Integrated Photonic Devices Dr. Lewis G. Carpenter, University of Southampton
16:10 – 16:30	Directly Driven Hexapod for Highly Dynamic Applications Dr. Thomas Haas, PI GmbH
16:30 – 16:50	The Marriage of Robots and Zeeko Machines - Steps Towards a Versatile, Automated, Manufacturing cell Richard Freeman, Zeeko Ltd
16:50 – 17:00	Closing Remarks Conference Team

ultraprecision.org







EPSRC Centre for Innovative Manufacturing &

Centre for Doctoral Training in Ultra Precision PhD Students

11:00-11:05	Welcome and Introduction Prof Bill O'Neill
11:05-11:08	Clare Collins Nanomaterial-Based Field Emission X-Ray Sources
11:08-11:11	Matt Bannister The Use of Ultrafast Laser Annealing to Remove Ion Beam Implanted Gallium
11:11-11:14	Adam Bennett Laser Assisted Reactive Atom Plasma Processing for Ultra Precision Engineering of Space Optics
11:14-11:17	Sam Brown Design and Development of Solid State Additive Manufacturing Techniques
11:17-11:20	Tianqi Dong Femtosecond Laser Direct Micro-Cutting Graphene for Device Applications
11:20-11:23	Wenhe Feng Ultra Precision Fabrication of Fused Silica Devices by Femtosecond laser Irradiation and Chemical Etching
11:23-11:26	Jiho Han High Power Laser System with Built-In Dynamic Beam Shaping Capabilities
11:26-11:29	George Meakin Ferroelectric Liquid Crystal Displays and Binary Dithering Schemes
11:29-11:32	Laurent Michaux Laser Induced Shock Wave Processing of Metallic Coatings
11:32-11:35	James Norman Advanced Technologies for Ultra Precise Light Weight Space Optics
11:35-11:38	Francisco Orozco Laser Processing of Carbon Nanotube Fibres and Films
11:38-11:41	Jon Parkins High Speed, High Power, Variable Focus Laser Additive Manufacturing of Metallic Biomedical Implants
11:41-11:44	Andy Payne Multiple Beam Powder Bed Fusion Additive Manufacturing
11:44-11:47	Matt Pryn Holography as a Consumer Display Solution
11:47-11:50	Jaliya Senanayake Holographic Enhancement of Fibre Optic Sensors
11:50-11:53	Yoanna Shams Digital Fabrication using Droplet Deposition and Ultrafast Laser Machining
11:53-11:56	Jason Ten High Speed Mask-Less Laser Controlled Precision Additive Manufacture
11:56-11:59	Chris Williamson High Speed Patterning of Individual Carbon Nanotubes
11:59-12:02	Chris Wright Ultra Precision Hybrid Laser FIB Platform
12:02-12:05	Peter Xia Diamond Machinable Coatings for Fluid Film Systems
12:05-12:08	Karen Yu Control System for Ultra Precision Processing
12:08-12:11	Nan Yu Advancement of Plasma Figuring Technology to Reduce MSF Errors on Metre-Scale Optical Surfaces